DECLARATION, POWER OF ATTORNEY AND PETITION

As a below named inventor, I hereby declare that:

My residence, post office address and citizenship are as stated below next to my name.

I believe I am an original, first and joint inventor of the subject matter which is claimed and for which a patent is sought on the invention entitled "WAVELENGTH DIVISION MULTIPLEXING AND DE-MULTIPLEXING SYSTEM" the specification of which

is attached hereto was filed on ****	as Application	Serial No.	****
and was amended	on	(if applica	ble).

I hereby state that I have reviewed and understand the contents of the above identified specification, including the claims, as amended by any amendment referred to above.

I acknowledge the duty to disclose information which is material to the examination of this application in accordance with Title 37, Code of Federal Regulations, § 1.56(a).

I hereby claim foreign priority benefits under Title 35, United States Code, § 119 of any foreign application(s) or U.S. provisional application(s) for patent or inventor's certificate listed below and have also identified below any foreign application or U.S. provisional application(s) for patent or inventor's certificate having a filing date before that of the application of which priority is claimed.

Prior Foreign/U.S. Provisional Application(s)

			Priority Claimed		
(Number)	(Country)	(Day, month, year filed)	 □ Yes	□ No	
(Number)	(Country)	(Day, month, year filed)	 □ Yes	□ No	
Number)	(Country)	(Day, month, year filed)	 □ Yes	□ No	

I hereby claim the benefit under Title 35, United States Code, § 120 of any United States application(s) listed below and, insofar as the subject matter of each of the claims of this application is not disclosed in the prior United States application in the manner provided by the first paragraph of Title 35, United States Code, § 112, I acknowledge the duty to disclose material information as defined in Title 37, Code of Federal Regulations, § 1.56(a) which occurred between the filing date of the prior application and the national or PCT international filing date of this application:

09/953,468	September 14, 2001	Pending
(Application Serial No.)	Filing Date	(Status: Patented, pending, abandoned)
(Application Serial No.)	Filing Date	(Status: Patented, pending, abandoned)

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

And I hereby appoint G.P. SMITH, REG. 20,142; A.C. ROSE, REG. 17,047; L.J. BOVASSO, REG. 24,075; C. BERMAN, REG. 29,249; C. DARROW, REG. 30,166; M.E. HARRIS, REG. 26,690; K.A. MACLEAN, REG. 31,118; C. ROSENBERG, REG. 31,464; M.E. BROWN, REG. 28,590; S.R. HANSEN, REG. 38,486; D.N. LARSON, REG. 29,401; J.W. INSKEEP, REG. 33,910; H.D. JASTRAM, REG. 19,777; B. CANTER, REG. 34,792; C.J. LERVICK, REG. 35,244; L. CULLMAN, REG.

39,645; C.A.S. HAMRICK, REG. 22,586; R.O. GUILLOT, REG. 28,852; J. BOYCE, REG. 40,920; C. CHOU, REG. 41,672; A.B. DIEPENBROCK III, REG. 39,960; M.K. BOSWORTH, REG. 28,186, L. SHERRY, REG. 43,918; L. McROSS, REG. 40,427; T. KHAN, REG. 46,273; L. GUERNSEY REG. 40,008; M. HUGHES, REG. 29,077; R. ROBERTS, REG. 38,597; S. HOWELL, REG. 45,929; R. NADER, 47,262; B. COLEMAN, REG. 39,145; P. HICKMAN, REG. 28,516; M. HUGHES, REG. 29,077; J. KUDLA, REG. 47, 724; D. BURTON, REG. 45,323; S. KELLEY, REG. 43,449; OPPENHEIMER WOLFF & DONNELLY LLP, 1400 Page Mill Road, Palo Alto, California 94304, (650) 320-4000, as my attorneys with full power of substitution and revocation, to prosecute said application and to transact in connection therewith all business in the Patent and Trademark Office and before competent International Authorities.

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Raymond E. Roberts OPPENHEIMER WOLFF & DONNELLY LLP

P.O. Box 10356 Palo Alto, California 94303

Wherefore I pray that Letters Patent be granted to me for the invention or discovery described and claimed in the foregoing specification and claims, and I hereby subscribe my name to the foregoing specification and claims, declaration, power of attorney, and this petition.

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Docket No.: 60617.3

WAVELENGTH DIVISION MULTIPLEXING AND DE-MULTIPLEXING SYSTEM

Inventors: TSAI, John C.; and WANG, David W.

Atty. ref.: 60617.300901

THIS CORRESPONDENCE CHART IS FOR EASE OF UNDERSTANDING AND INFORMATIONAL PURPOSES ONLY, AND DOES NOT FORM A PART OF THE FORMAL PATENT APPLICATION.

1	fiber Bragg grating	240	light beam	
2	grating region	242	strayed portions	
3	interlayer	244	interface	
4	laser beam	246	interface	
5	reflected beam	248	reflected portion	
6	passed beam	250	passed portion	
100	Bragg grating	302	substrate	
102	laser beam	304	grating region	
104	substrate	306	mask	
106	reflective layer	308	grating pattern	
108	grating region	310	interlayer array	
110	interlayer			
112	first transmissive material	400	process	
114	second transmissive material	402-4	12 step	
116	over-fill layer	422-40	sub-step	
118	reflected beam			
120	passed beam	500	linear grating	
		502	background material	
202	substrate	504	interlayer material	
204	photoresist layer	506	thickness	
204a	unexposed region	508	separation	
204b	exposed region	510	light beam	
206	photomask	512	reflected beam	
208	pre-designated pattern	514	passed beam	
212	light			
214	transmissive layer	600	planar grating	
216	air gap	602	background	
218	photoresist layer	604	cells	
218a	unexposed region	606	XYZ-axes icon	
218b	exposed regions	608	thickness	
220	photomask	610	separation	
222	grating pattern	612	thickness	
224	light	614	separation	
226	grating region	616	light beam	
228	over-fill layer	618	diffracted beam	
230	interlayer array	620	passed beam	
232	transmissive layer			
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700	cubical grating	1006	WDM device
702	background	1008	light beam
704	cells	1010	light target
706	XYZ-axes icon		
708	light beam	1100	de-multiplexing system
710	first diffracted beam	1102	light source
712	second diffracted beam	1104	light beam
714	passed beam	1106	WDM device
,	pubbou bourn	1108	light beams
800	generic grating	1110	light targets
802	background	1110	nght targets
804	cell	1200	multiploving dovice
			multiplexing device
806	thickness	1202	first planar grating
808	light beam	1204	second planar grating
810	first surface	1206	third planar grating
812	first reflected portion	1208	first input beam
814	first refracted portion	1210	second input beam
816	second surface	1212	third input beam
818	second reflected portion	1214	fourth input beam
820	transmitted portion	1216	first output beam
822	second refracted portion	1218	second output beam
826	vertical separation	1220	third output beam
828	horizontal separation		
830	vertical separation	1300	multiplexing device
	•	1302	first cubical grating
850	grating	1304	second cubical grating
852	background	1306	third cubical grating
854	cells	1308	first input beam
856	horizontal thickness	1310	second input beam
858	vertical thickness	1312	third input beam
860	horizontal separation	1314	fourth input beam
862	first vertical separation	1314	fifth input beam
864	second vertical separation	1318	sixth input beam
866	first portions	1310	seventh input beam
868	•		-
	first portions	1322	first output beam
868	second portions	1324	second output beam
000		1326	third output beam
880	grating	1 400	1 1. 1 . 1 . 1
882	cells	1400	de-multiplexing device
884	first portions	1402	first planar grating
886	second portions	1404	second planar grating
888	third portions	1406	third planar grating
		1408	input beam
1000	multiplexing system	1410	first diffracted beam
1002	light sources	1412	first intermediate beam
1004	light beam	1414	second diffracted beam

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1416	second intermediate beam	1602	center grating block
1418	third diffracted beam	1604	first grating block
1420	output beam	1606	second grating block
	-	1608a	-f cubical gratings
1500	de-multiplexing device	1610a	-f gratings
1502	first cubical grating	1612a	-f gratings
1504	second cubical grating	1614	input beam
1506	third cubical grating	1616	input source
1508	input beam	1618	first output beam
1510	first diffracted beam	1620	first output target
1512	second diffracted beam	1622	second output beam
1514	first intermediate beam	1624	second output target
1516	third diffracted beam		_
1518	fourth diffracted beam	1700	interleaver
1520	second intermediate beam	1702	first input beam
1522	fifth diffracted beam	1704	second input beam
1524	sixth diffracted beam	1706	first input source
1526	output beam	1708	second input source
		1710	output beam
1600	de-interleaver	1712	output target
1602	center drating block		